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Fundamental processes in III-V  
photocathodes; application for  
high-brightness photoinjectors

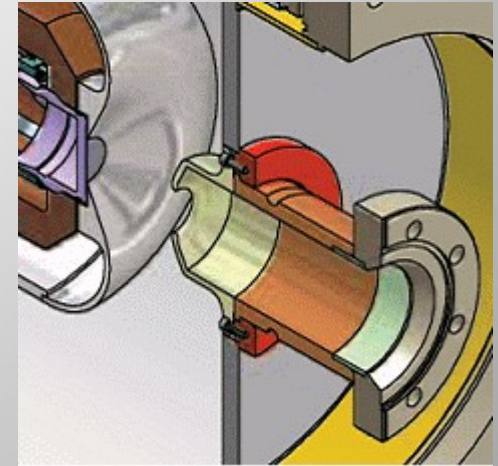


- Motivation
- NEA photoemission
- Some practical aspects
- Study cases: GaAs, GaAsP, GaN
- Summary



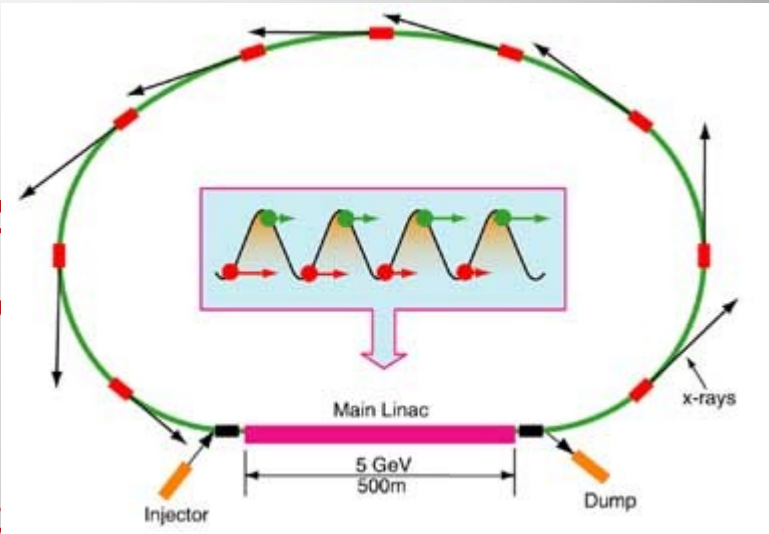
# Why are we interested?

- Photoinjectors: a photocathode in high electric field ( $\gg$  MV/m), either DC or RF
- Relativistic electrons can be further accelerated in a linac (linear accelerator) without degradation of beam brightness:
  - CW ultra-bright x-ray sources; high power FELs
  - Electron-ion colliders and ion coolers
  - Ultrafast electron diffraction, etc.



- *Energy recovery linac*: a new class of accelerators in active development

- Essentially removes the average current limitation typical to linacs



typical to linacs (i.e.  $P_{\text{beam}} \gg P_{\text{wall plug}}$ )

$P_{\text{wall plug}}$ )

- Average currents 10's to 100's of mA can be efficiently accelerated (and de-accelerated)



- QE and photon excitation wavelength

$$i(\text{mA}) = \frac{\lambda(\text{nm})}{124} \times P(\text{W}) \times \text{QE}(\%)$$

- E.g. 1 W of  
775 nm (Er-fiber  $\lambda/2$ )  $\Rightarrow$  6.2 mA/%  
520 nm (Yb-fiber  $\lambda/2$ )  $\Rightarrow$  4.2 mA/%  
266 nm (Nd-glass  $\lambda/4$ )  $\Rightarrow$  2.1 mA/%

- Transversely cold (thermalized) electron distribution

- Directly sets the solid angle of the emitted electrons; an upper limit on achievable beam brightness

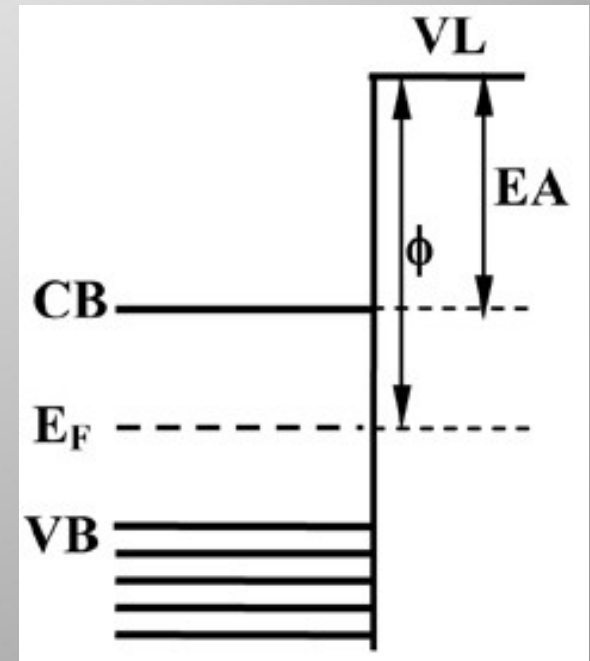


- **Prompt response time**
  - A picosecond response is essential to take advantage of the space charge control via laser pulse shaping
- **Long lifetime and robustness**
  - Extraction of many 100's to 1000's of C between activations are necessary to make the accelerator practical

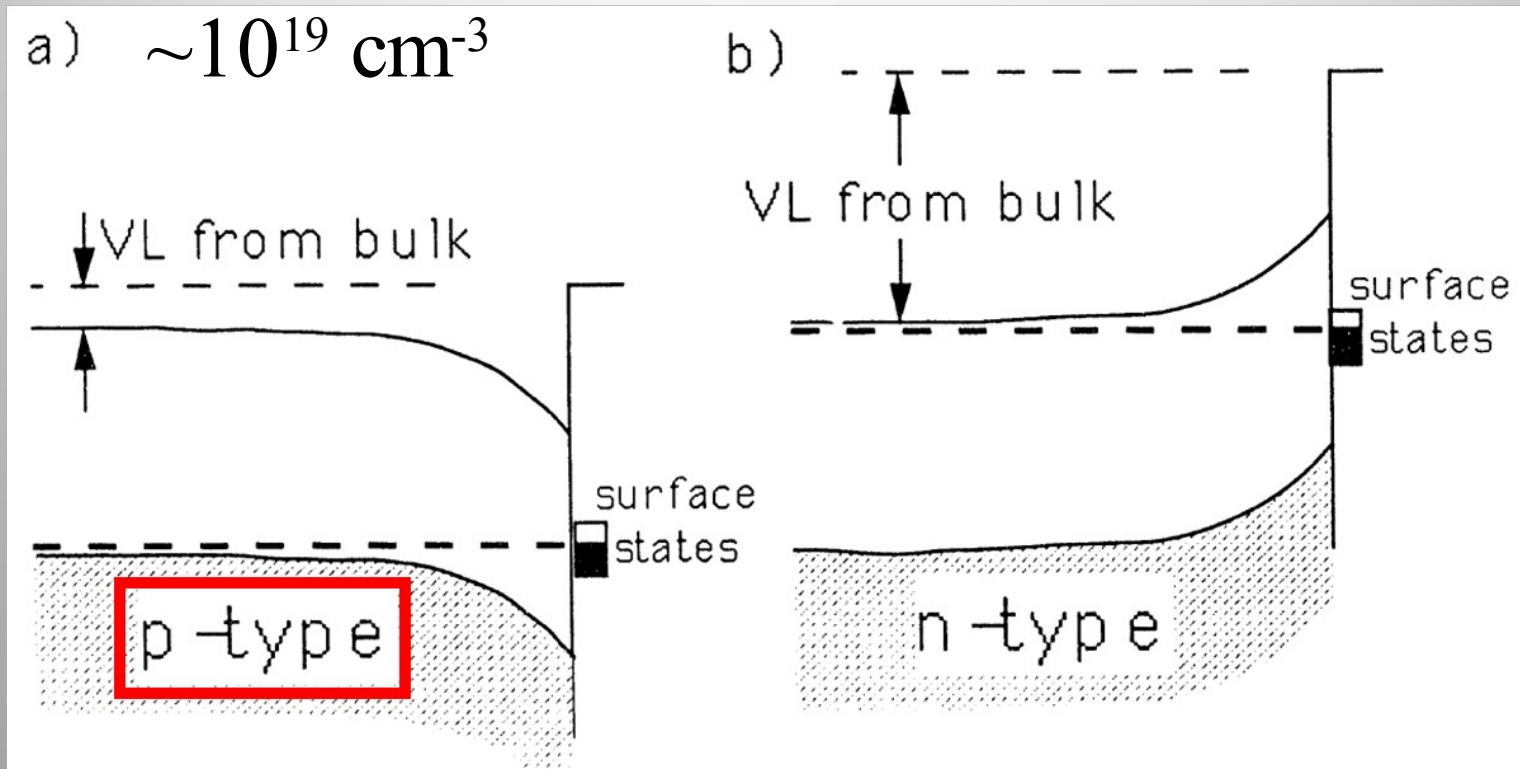


# Negative electron affinity

- Defined as vacuum level  $E_{\text{vac}}$  relative to the conduction band minimum
- Negative affinity: the vacuum level lies below the CBM  
 $\Rightarrow$  very high QE possible
- NEA:
  - 1) band bending
  - 2) dipole layer







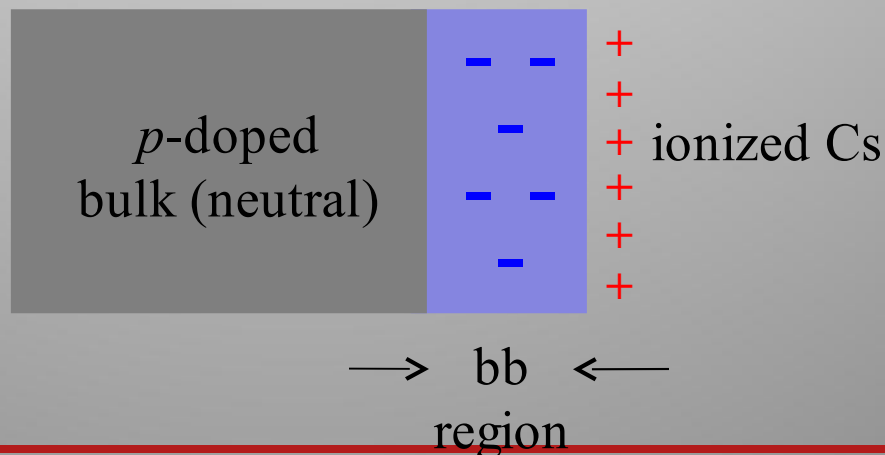
- Alperovich et al., Phys. Rev. B **50** (1994) 5480: clean p-doped GaAs has Fermi level unpinned and shows little band bending





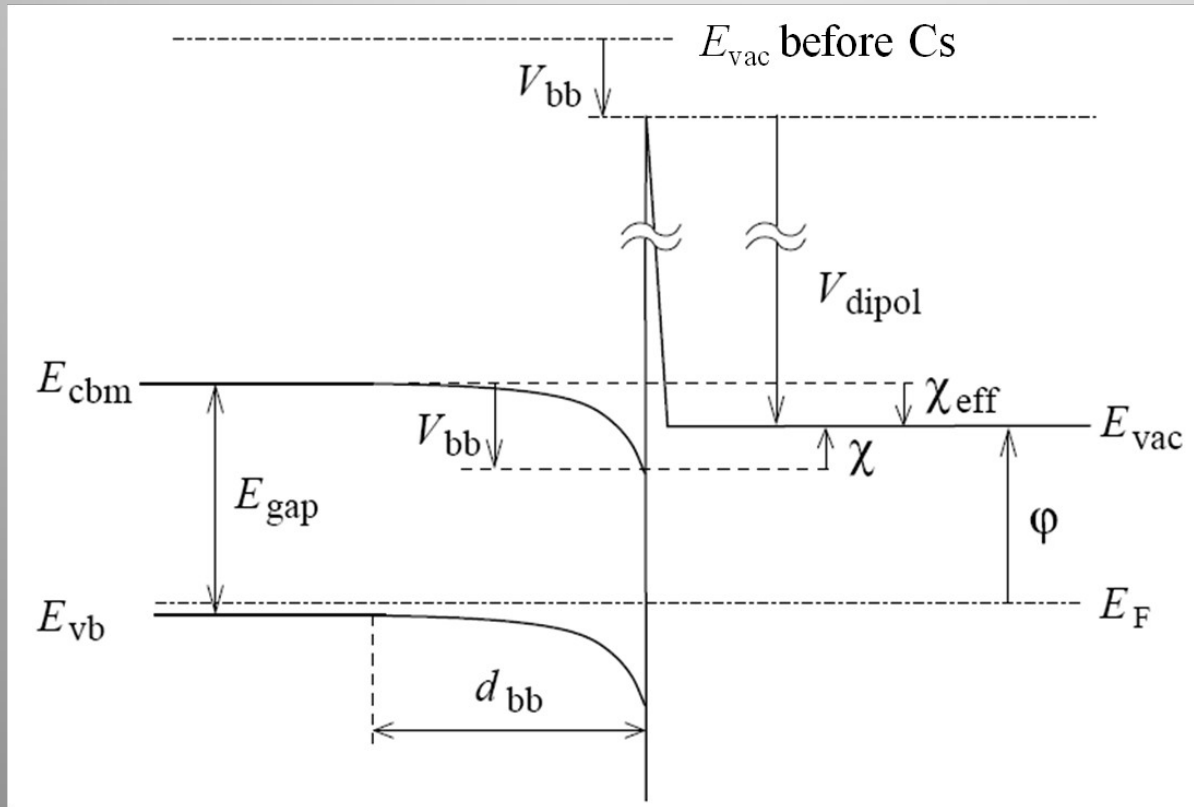
# NEA: Cs ~monolayer

- Cs was found to play a larger role for NEA instead:
  - 1) band bending through donor surface states, and
  - 2) dipole surface layer from polarized Cs adatoms
  - Cs-induced donor-like surface states contribute their electrons to the bulk
  - Hole depleted region (negatively charged acceptors) lead to band bending region



# NEA: ~Cs monolayer (contd.)

- Majority of Cs atoms become only polarized (not ionized), forming a dipole layer (e- Cs+)



***GaAs***

$$E_{gap} = 1.42 \text{ eV}$$

Before Cs

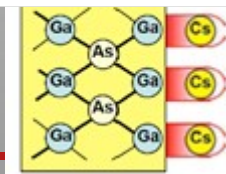
$$\chi = 4 \text{ eV}$$

After Cs

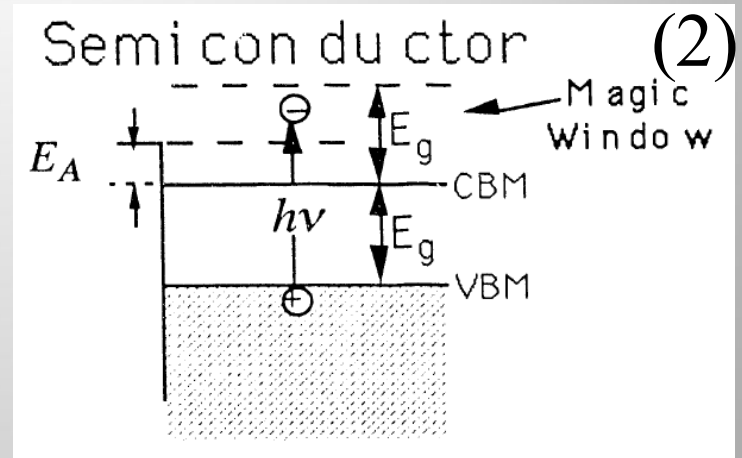
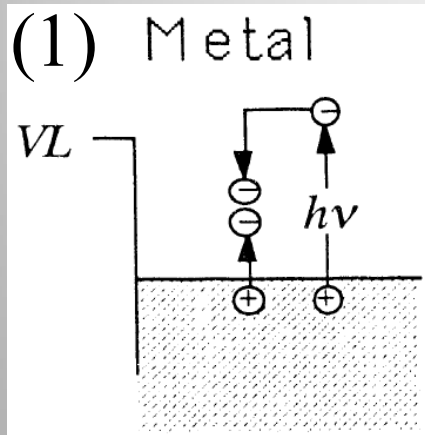
$$\chi_{eff} \sim -0.1 \text{ eV}$$

$$V_{bb} \sim 0.4 \text{ eV}$$

$$d_{bb} \sim 10 \text{ nm}$$



# Spicer's magic window

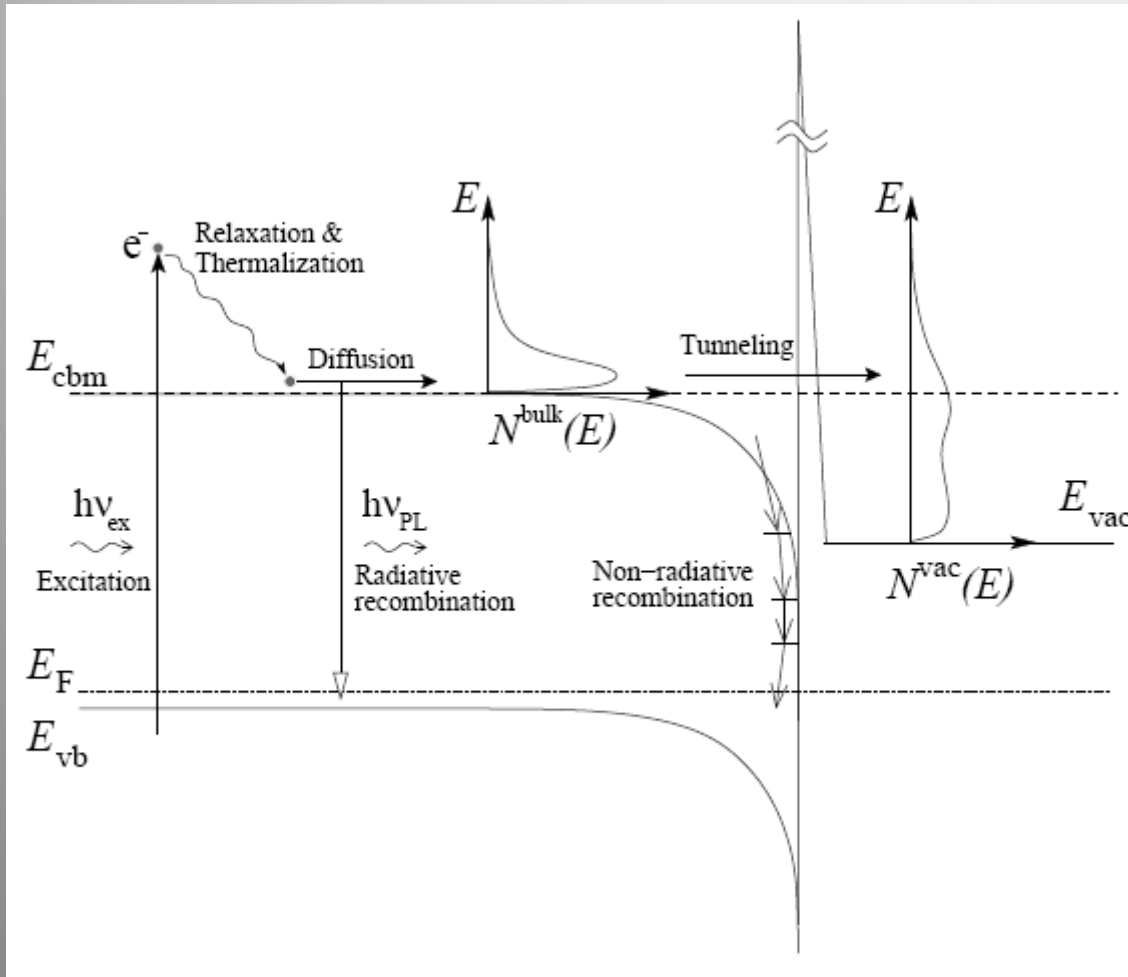


(1) *electron-electron* scattering: typical of metals, large energy loss per collision

(2) *electron-phonon* scattering: slowly depletes excessive energy of excited electron (LO phonons in GaAs  $\sim 35$  meV)

“*Magic window*”: in semiconductors, one needs excess  $KE > E_{gap}$  for  $e^-/e^-$  scattering. Thus, electrons excited with  $E_{vac} < KE < E_{VBM} + 2E_{gap}$  have excellent chances of escape

# Electron transport processes



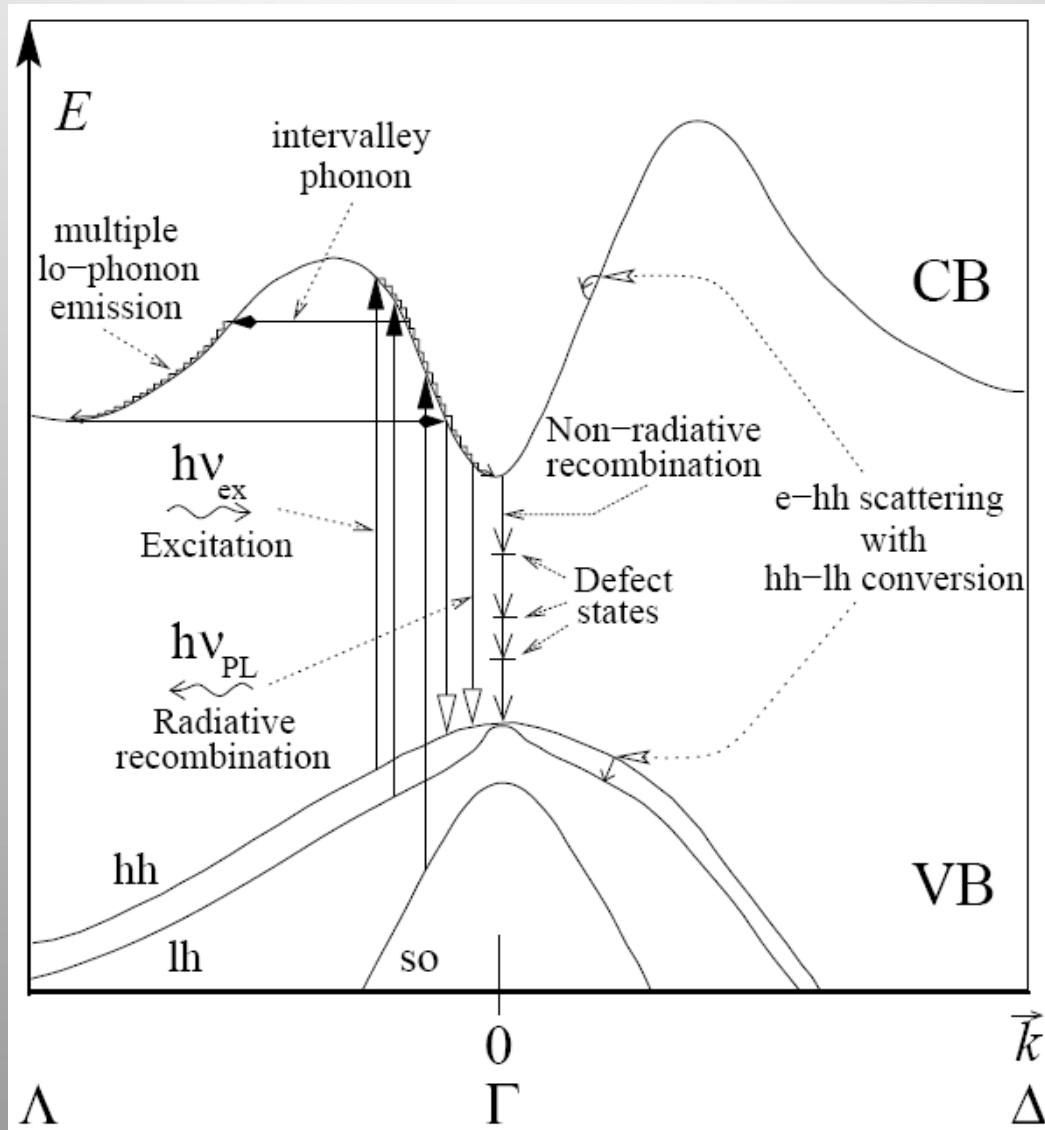
CBM thermalization  
time: 0.1-1 ps

Electron-hole  
recombination: ~ns

Emission time:  
 $\propto 1/(\alpha^2 D)$

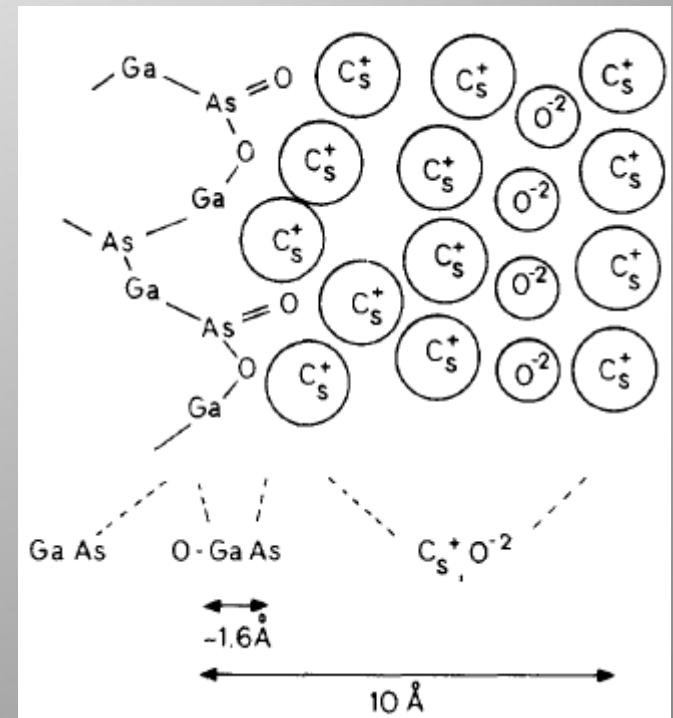
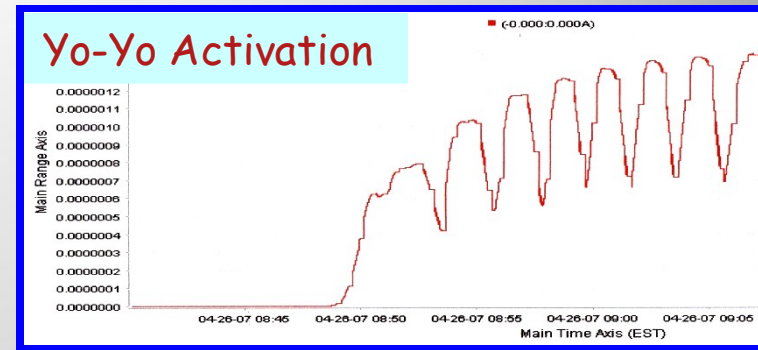
strong wavelength  
dependence

# Energy vs. momentum



# Role of fluorine/oxygen

- Routine “yo-yo” activation employs  $O_2$  or  $NF_3$
- Further reduction of affinity consistent with a double dipole model
- Stabilizes Cs on the surface; no lifetime or otherwise apparent advantage for either gas
- Bonded unstable nitrogen is found on Cs- $NF_3$  activated surfaces (APL 92, 241107)



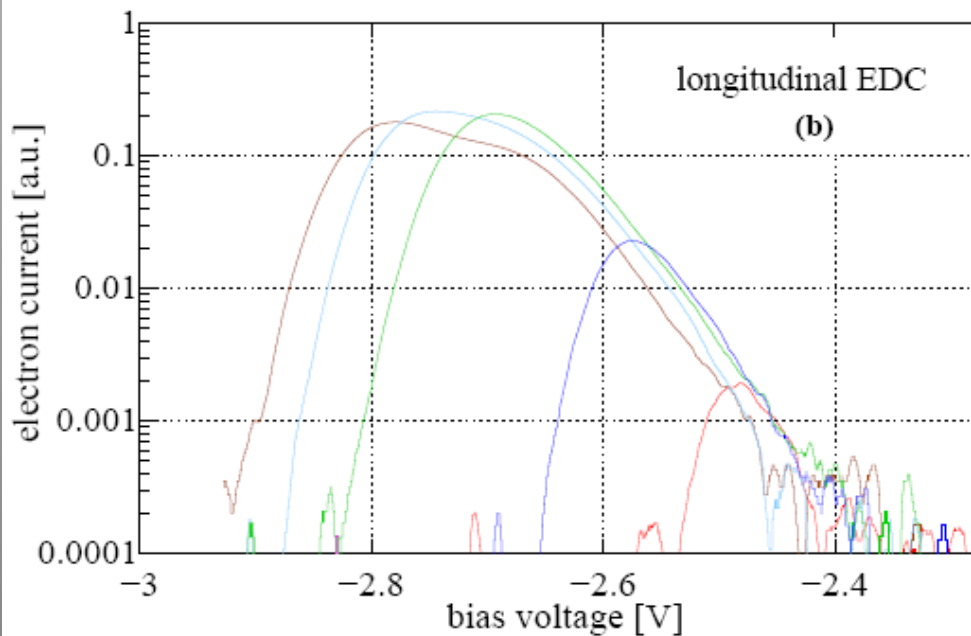
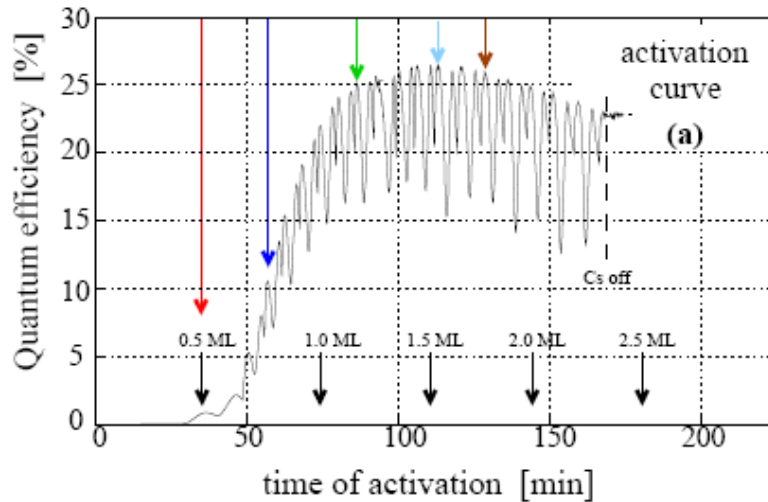
*JAP 54 (1983) 1413*





# GaAs: Optimal Cs coverage

*laser wavelength: 670 nm*

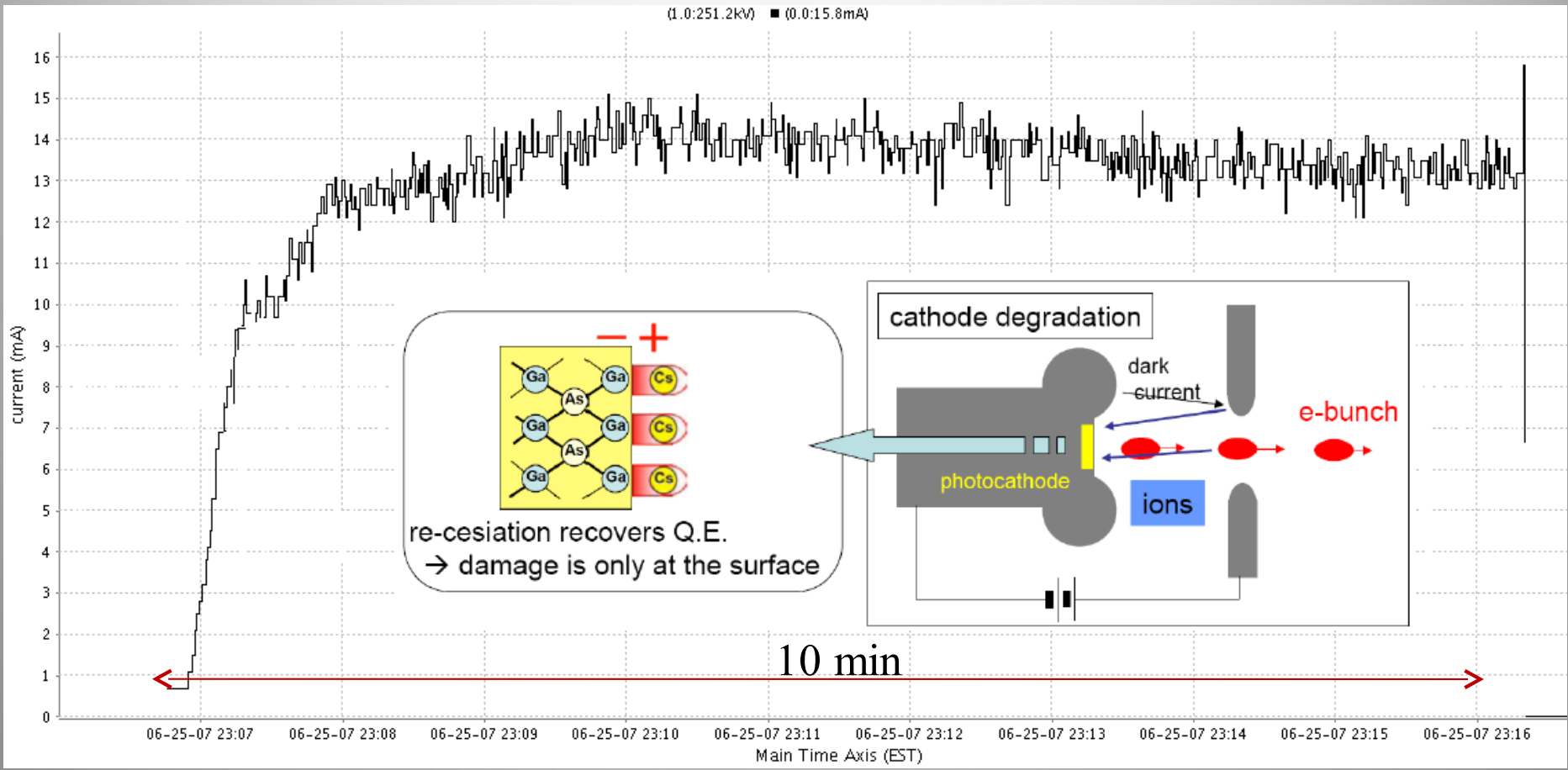


*Ugo Weigel, PhD thesis*





- $\text{H}_2\text{O}$ ,  $\text{CO}_2$  and  $\text{O}_2$  can lead to chemical poisoning of the activated layer
- Low current ( $\sim 1\mu\text{A}$ )  $1/e$  lifetimes  $\sim 100$  hours typical in our prep chambers
- 3-5 times better in the DC gun (low  $10^{-12}$  Torr vacuum)
- High average current (mA's) lifetime limited by ion backbombardment



- ~5 hour lifetime (limited by gas backstreaming from the beam dump), i.e. 20 hours 1/e for 5 mA



- Our group has been evaluating III-V photocathodes
  - Transverse energy of electrons (thermal emittance)
  - Measure the photoemission response time
- Materials studied so far
  - GaAs @ 450-850nm: JAP 103, 054901; PRST-AB 11, 040702
  - GaAsP @ 450-640nm: Ibid
  - GaN @ 260nm: JAP 105, 083715



$$\frac{\partial c(h, t)}{\partial t} = D \frac{\partial^2 c(h, t)}{\partial h^2}$$

subject to:

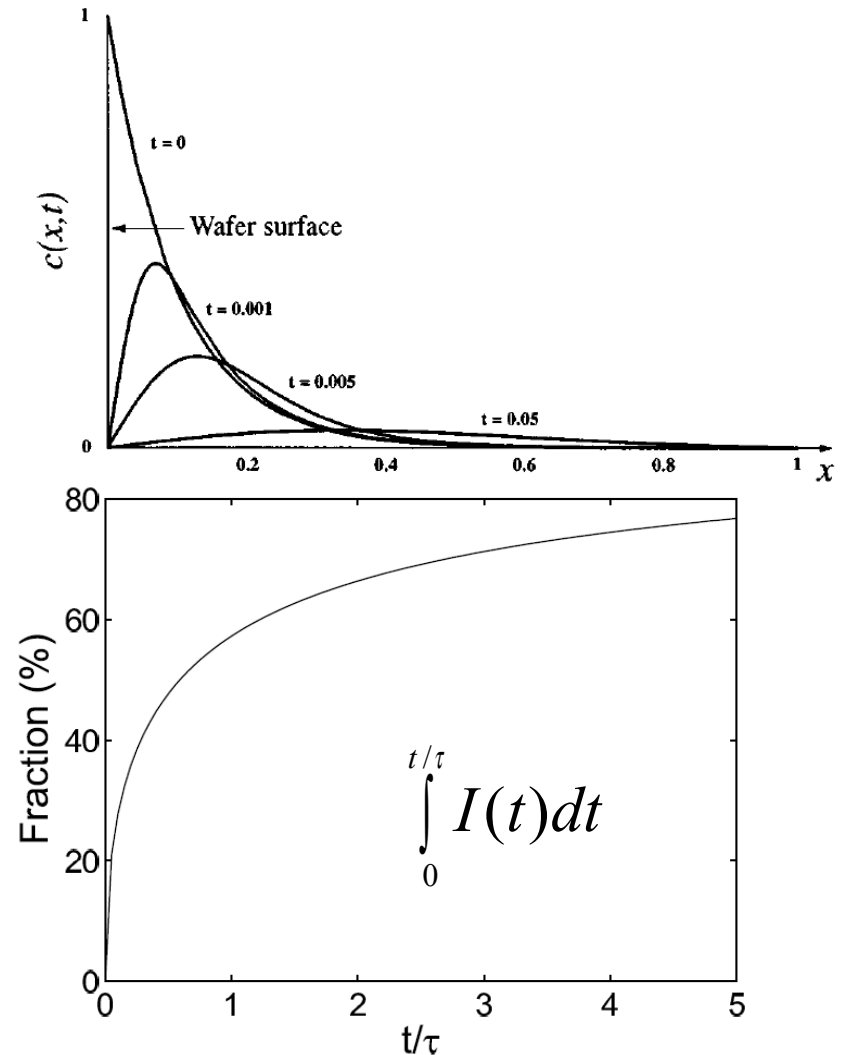
$$c(h, t = 0) = c_0 e^{-\alpha h}$$

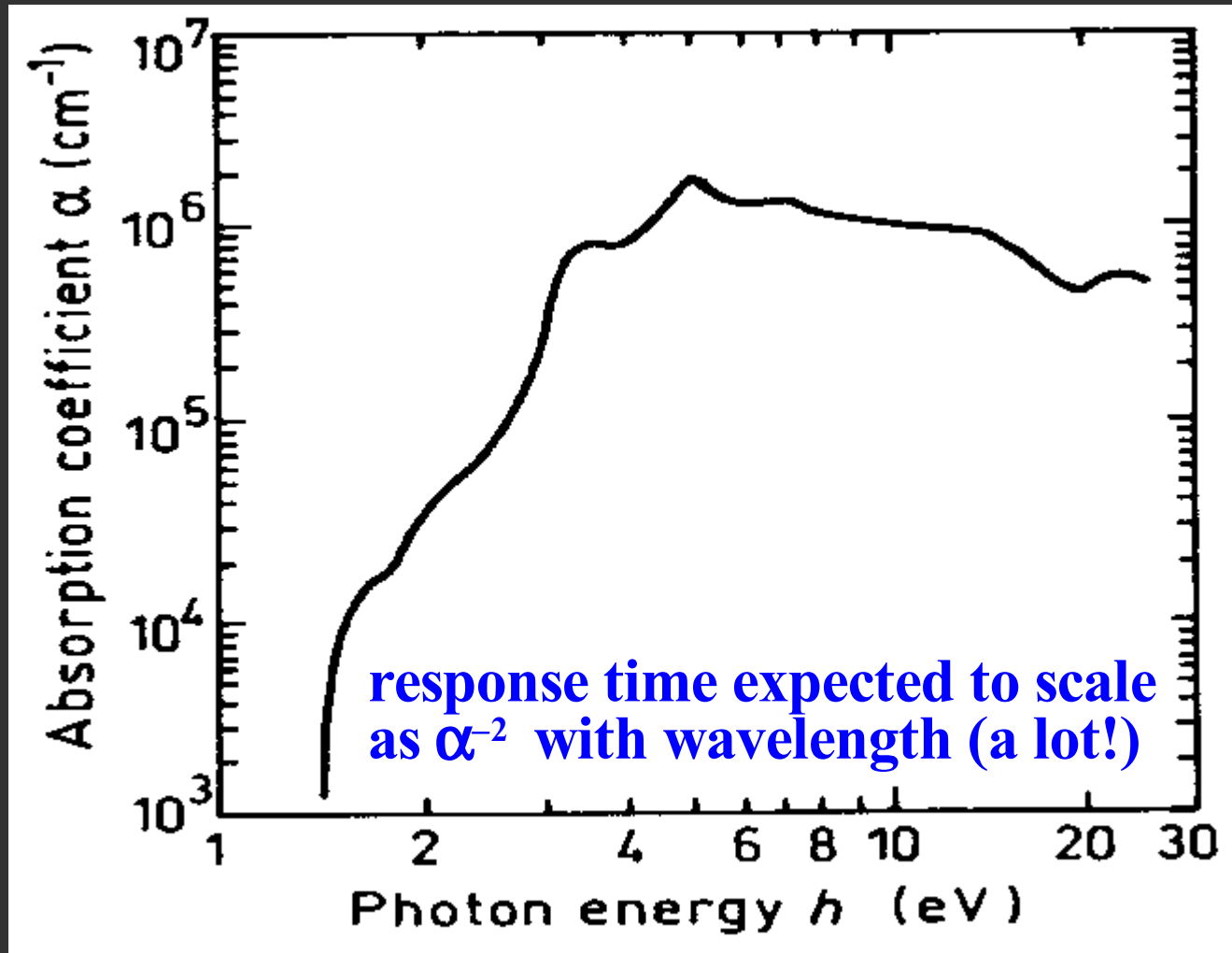
$$c(h = 0, t) = 0$$

$$I(t) \propto \frac{\partial}{\partial t} \int_0^{\infty} c(h, t) dh.$$

$$I(\kappa) \propto \frac{1}{\sqrt{\pi \kappa}} - \exp(\kappa) \operatorname{erfc}(\sqrt{\kappa})$$

$$\kappa \equiv t/\tau, \text{ where } \tau \equiv \alpha^{-2} D^{-1}$$

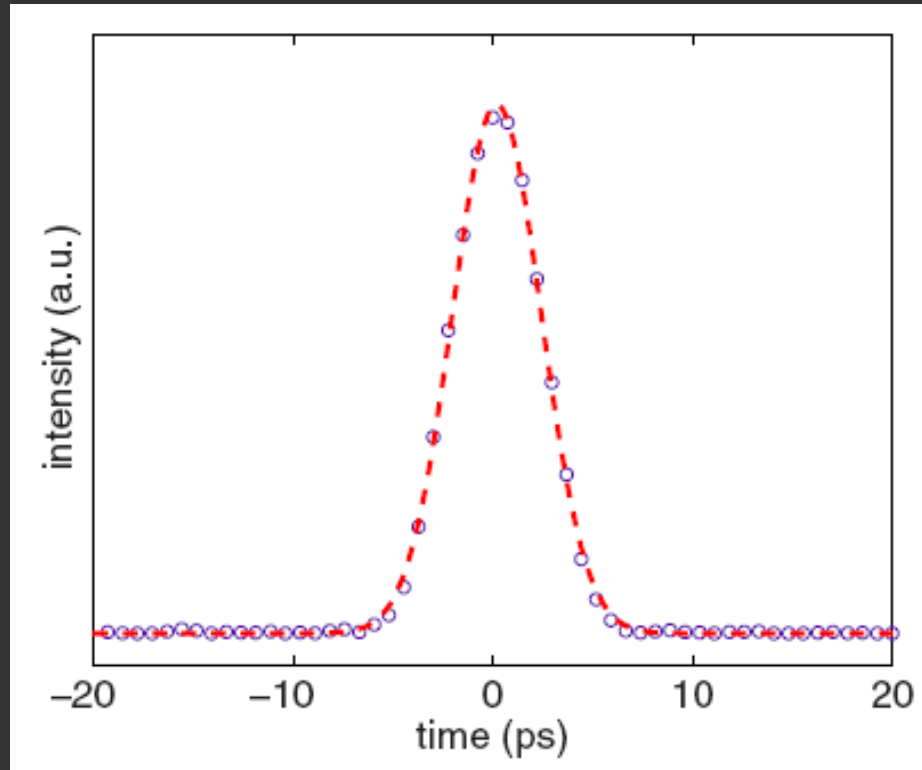
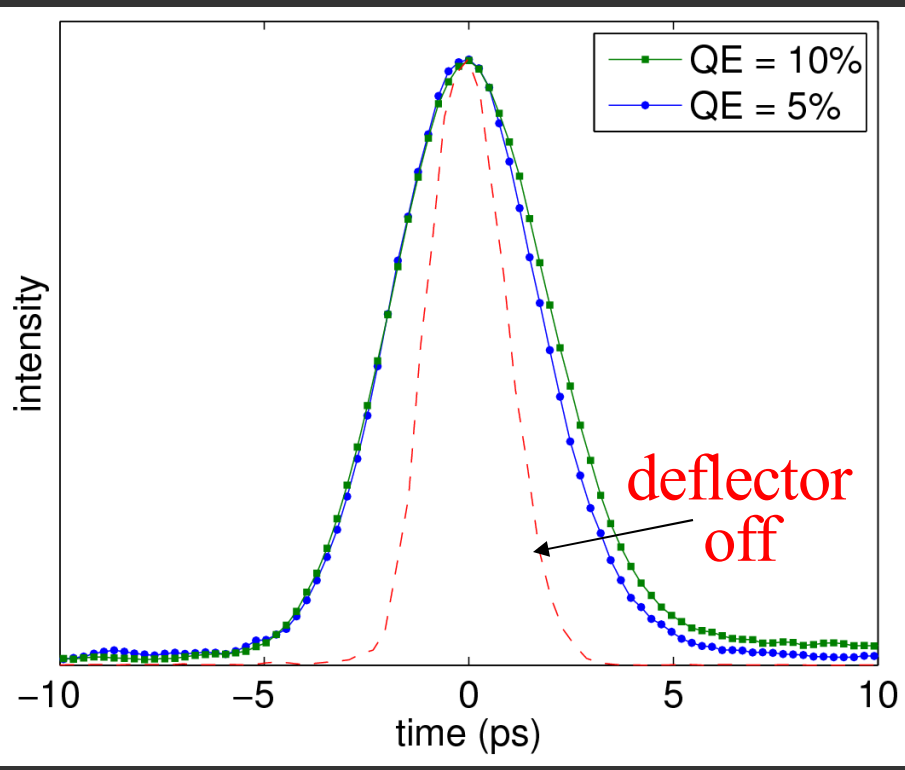






## GaAs @ 520 nm

## GaN @ 260 nm

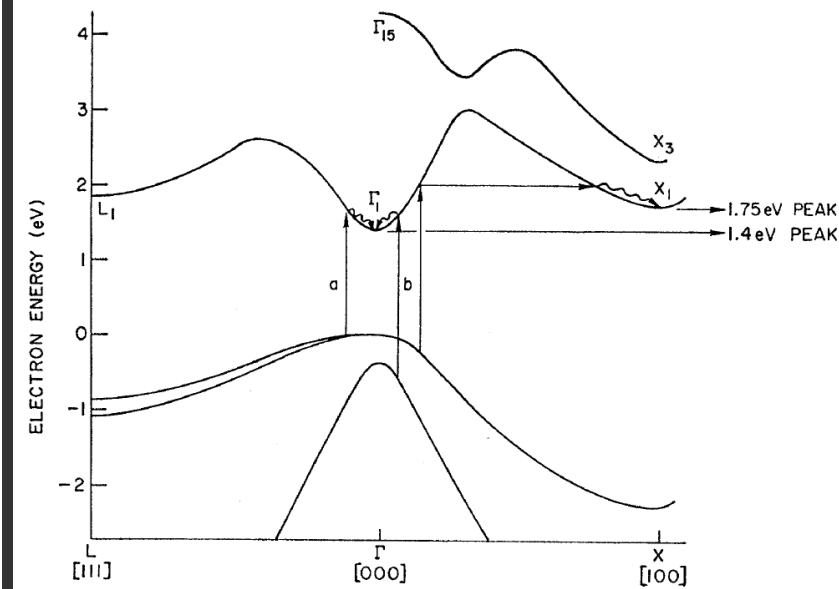
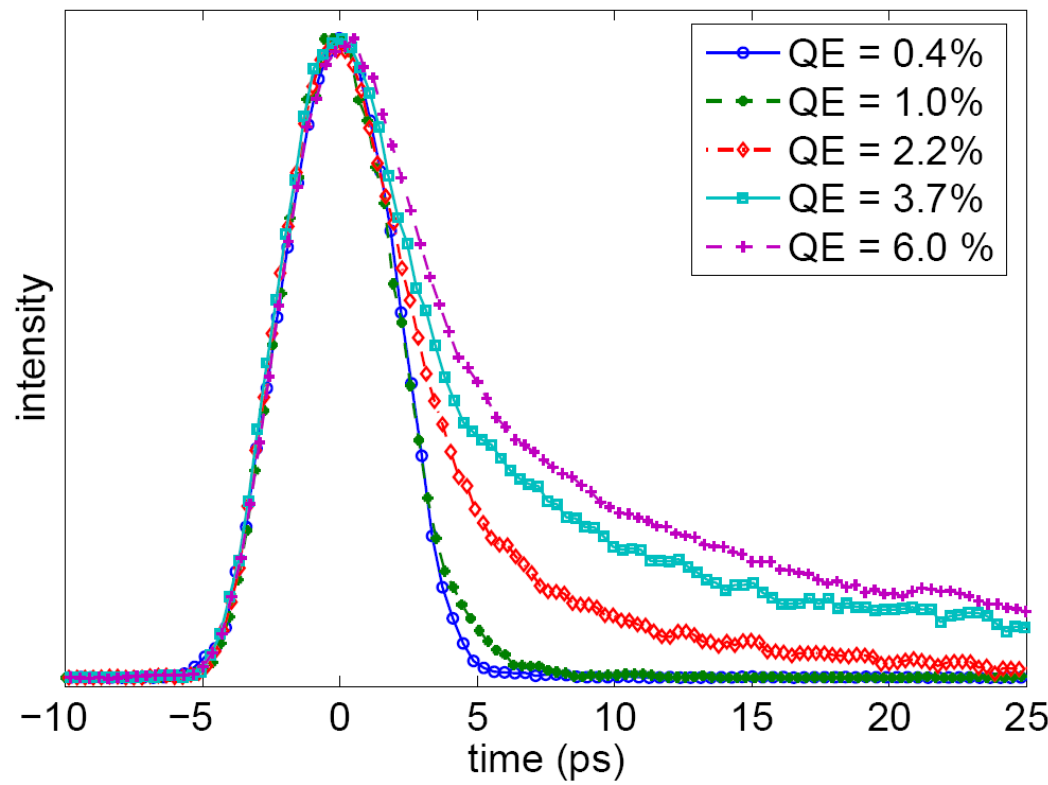


Measurements done by transverse deflecting RF cavity  
Limited by 1.8 ps rms resolution dominated by laser to RF synchronization



## GaAsP @ 520 nm

P concentration 45%



## Strong QE dependency

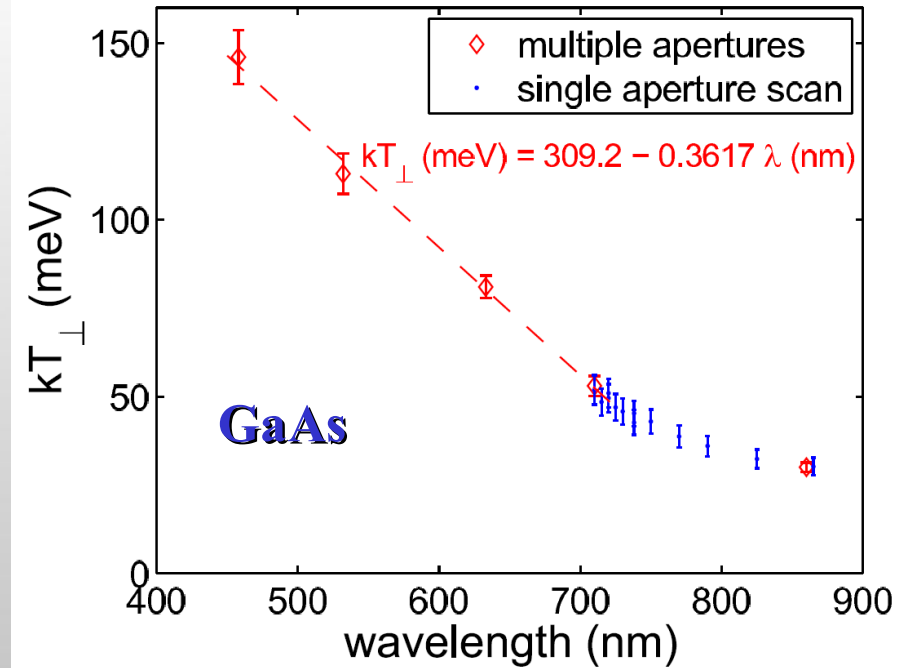
Two valleys:  $\Gamma$  (direct) and X (indirect) involved in the process





# Transverse energy distributions

- No surprises for bulk GaAs: cold electrons with a near band-gap excitation
- Surprisingly large transverse energy spread for GaN and GaAsP:



- GaAsP:  $kT_{\perp} = 130\text{-}240$  meV for photons 0-780 meV photons above the band-gap
- GaN:  $kT_{\perp} = 0.9$  eV for photons with 1.4 eV above the band-gap



- Transverse energy of photoelectrons remain poorly understood for III-V semiconductors (other than GaAs)
- More carefully controlled experimental data on transverse energy distributions/time response needed
- Predictive codes and models need to be developed and benchmarked with experiments
- This will allow photocathode engineering with the desired characteristics such as cold electrons with a ps response



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